IN THE CLAIMS

Please amend claim 31.

Please cancel claims 32-39, and please add claims 40-51.

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31. (Thrice Amended) A gate electrode comprising:

an insulative layer disposed on a substrate;

a uniform cross-section gate layer disposed on said insulative layer;

thin first spacers disposed adjacent to opposite sides of said gate layer;

thin second spacers disposed adjacent to opposite sides of said thin first spacers;

thin third spacers disposed adjacent to opposite sides of said thin second spacers;

thick fourth spacers disposed adjacent to opposite sides of said thin third spacers; and

a conductive layer disposed on said gate layer, wherein at least part of the conductive

layer is wider than said gate layer.

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(New) The gate electrode of claim 31, wherein the conductive layer has a non-uniform cross-section defined by a narrower base section which is in contact with the gate layer, and a wider top section.

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(New) The gate electrode of claim 40, wherein the thin first spacers and the thin second spacers are deformed to accommodate the wider top section of the conductive layer.

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42. (New) The gate electrode of claim 40, wherein the part of the conductive layer that is wider than the gate layer rests on at least the first thin spacer.

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(New) The gate electrode of claim 31 wherein said insulative layer comprises an
oxide.
(New) The gate electrode of claim 43 wherein said gate layer comprises a
polysilicon.
128 1/ 45. (New) The gate electrode of claim 44 wherein said conductive layer comprises a
polycide.
129 /
46. (New) The gate electrode of claim 45 wherein said thin first spacers comprise an oxide.
130 47. (New) The gate electrode of claim 46 wherein said thin second spacers comprise a
nitride.
131
484 (New) The gate/electrode of claim 47 wherein said thin third spacers comprise an
oxide.
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49. (New) The gate electrode of claim 48 wherein said thick fourth spacers comprise a nitride.
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50. (New) The gate electrode of claim 49 wherein said polycide comprises titanium
salicide (TiSi ₂).

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